



# Characterization of TESLA-shaped single-cell Nb thin-film cavity with varying RRR values at low temperatures.

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# Superconducting Quantum Materials and Systems Center



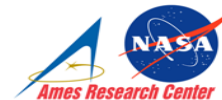
With the **Superconducting Quantum Materials and Systems Center (SQMS)**, we propose to bring the power of DOE laboratories, together with industry, academia and other federal entities, to achieve transformational advances in quantum technologies for computing and sensing”



Northwestern  
University



AMES LABORATORY  
Creating Materials & Energy Solutions  
U.S. DEPARTMENT OF ENERGY



NIST



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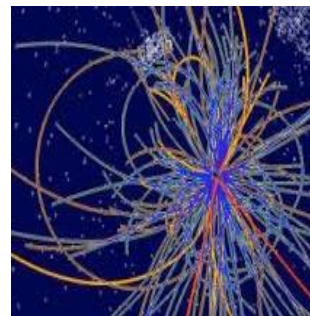
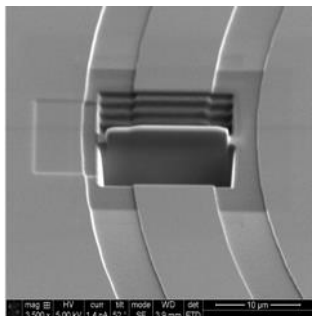
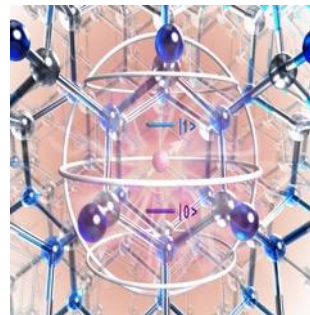
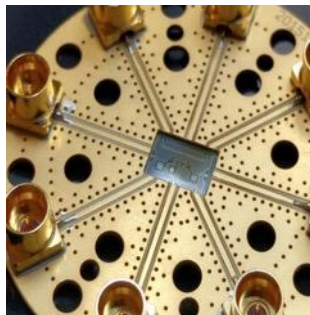
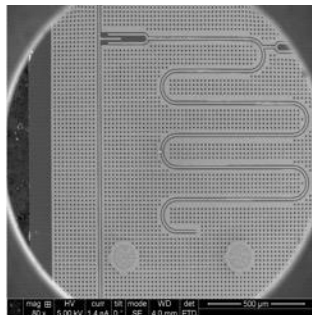
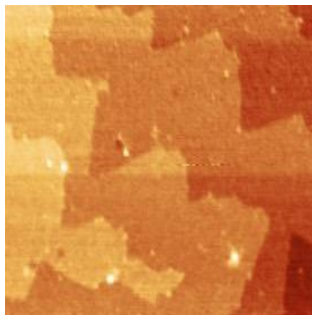
JANIS

Unitary Fund

20 Institutions  
>275 Collaborators

❖ We have the ambitious goal of building the first quantum computer at Fermilab

# SQMS S&T Innovation Chain: from material discovery to quantum advantage





# SRF cavity and Nb thin-film characteristics



## Cavity parameters

- ❖ Type: TESLA-shaped single-cell Nb
- ❖ Frequency: 1.3GHz
- ❖ Beta: High
- ❖ Geometry factor: 273 $\Omega$

## Thin-film deposition parameters

- ❖ Main pulse duration: 200us
- ❖ Bias voltage: -75V
- ❖ Power: 1200W
- ❖ Pressure: 3x10<sup>-3</sup>mbar
- ❖ Temperature: 150°C
- ❖ Deposition time: 6 hours
- ❖ Target: Nb RRR300
- ❖ Background gas: Kr
- ❖ Thickness: 6 $\mu$ m

Data: CERN

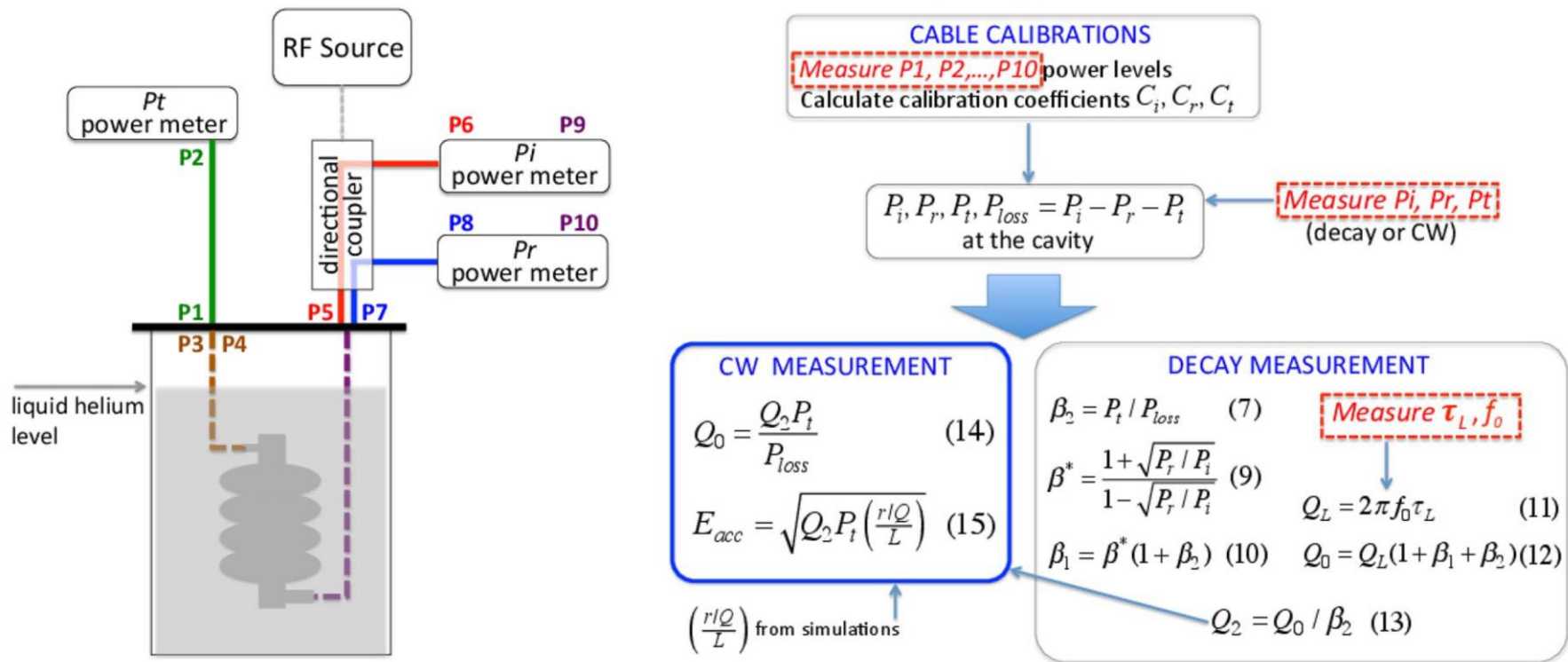
Nb cavity was designed and fabricated at Fermilab. Nb thin film was optimized and coated at CERN



A Bipolar HiPIMS thin film deposition system at CERN. (Image: CERN)

**Motivation:** The superconducting properties of niobium in microwave fields vary significantly with lattice defects and impurity content, where sub-at.% impurity level can reduce or increase microwave surface resistance.

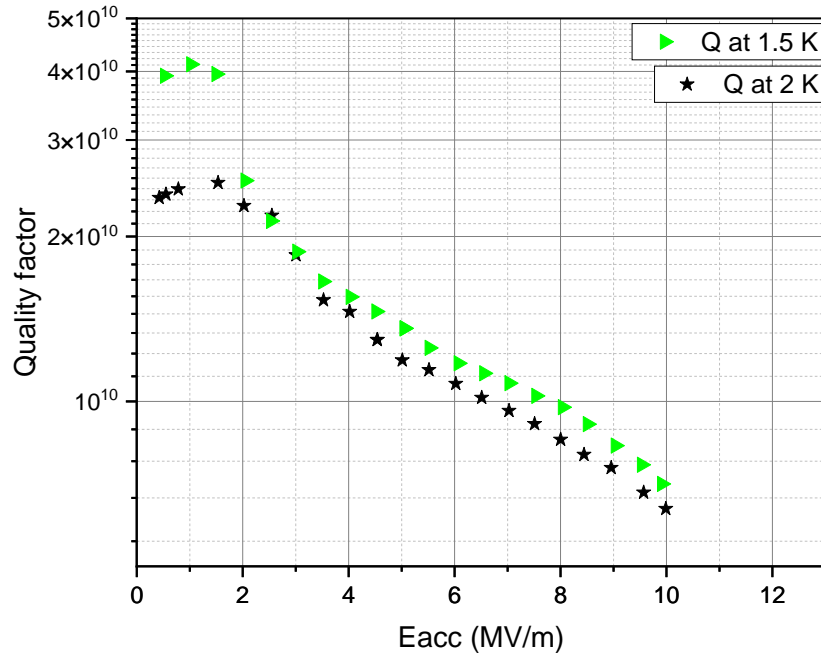
# Vertical Test Stand (VTS) cavity testing



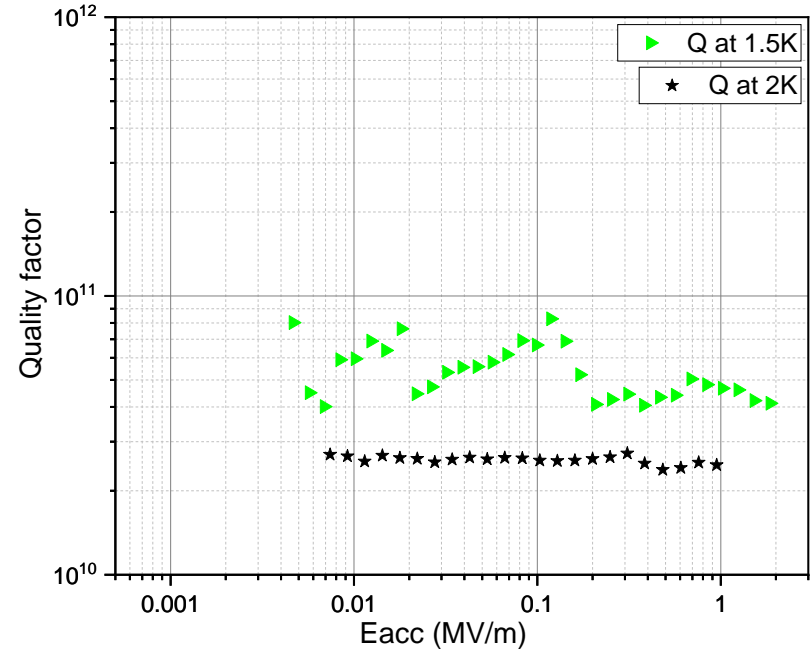
O. Melnychuk, A. Grassellino, A. Romanenko "Error analysis for intrinsic quality factor measurement in superconducting radio frequency resonators"

# VTs measurements

Accelerating gradient vs Quality factor

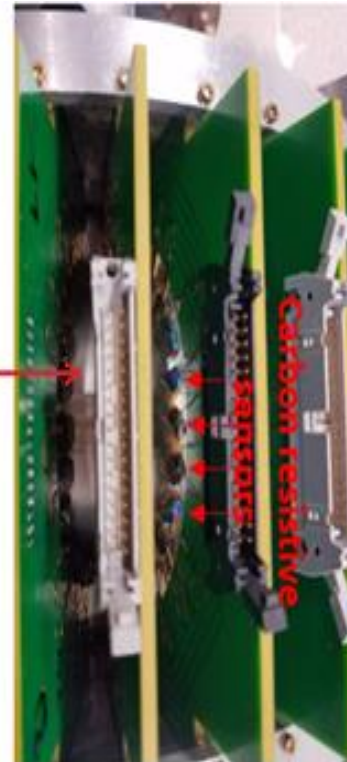
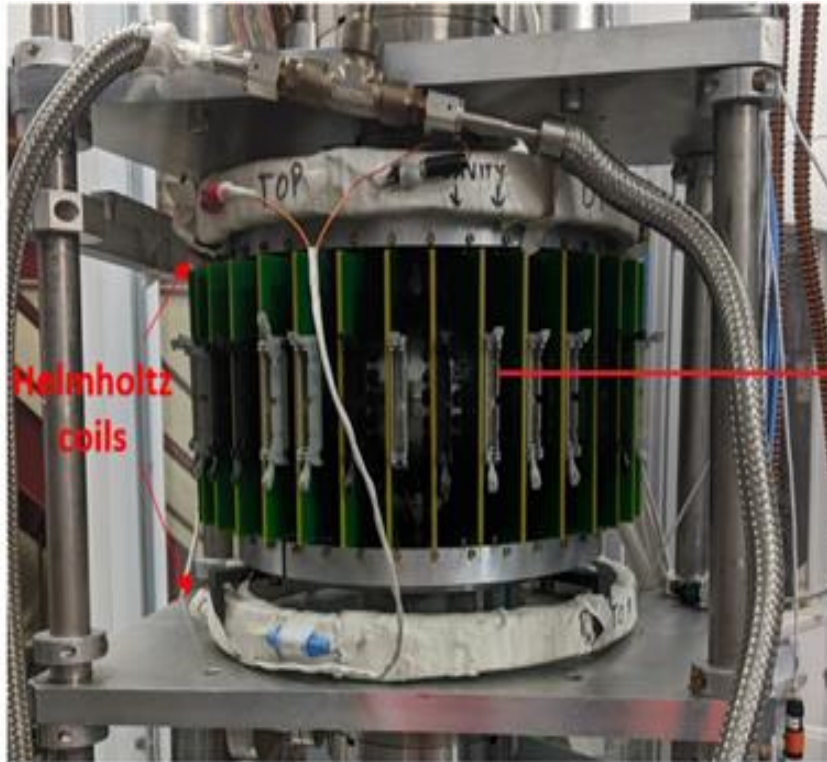


Accelerating gradient vs Quality factor at low field



❖ The cavity was limited at  $E_{acc} \approx 10.2$  MV/m by a quench.

# Thermometry Mapping

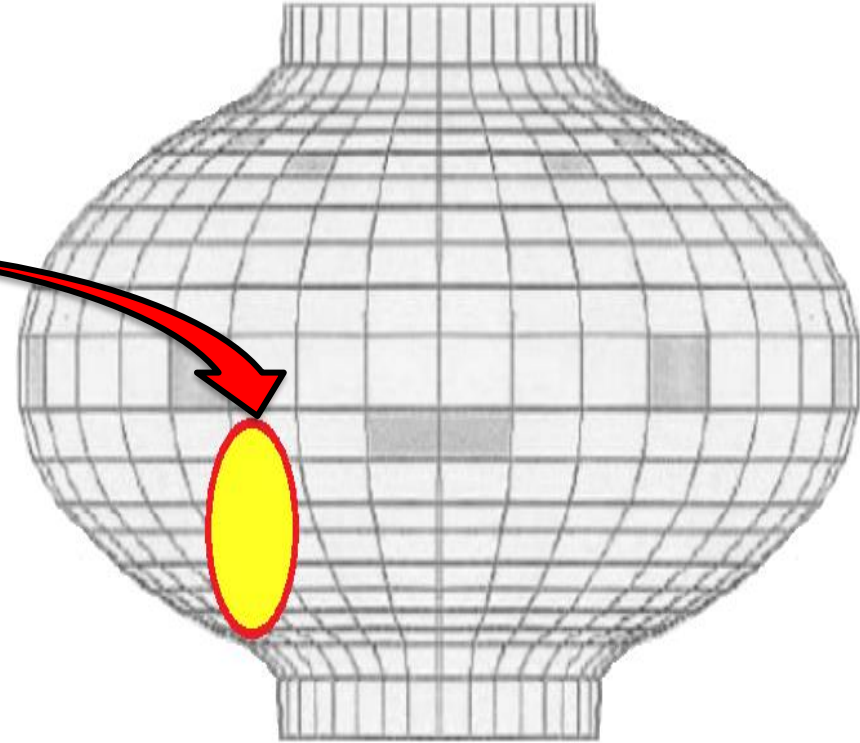
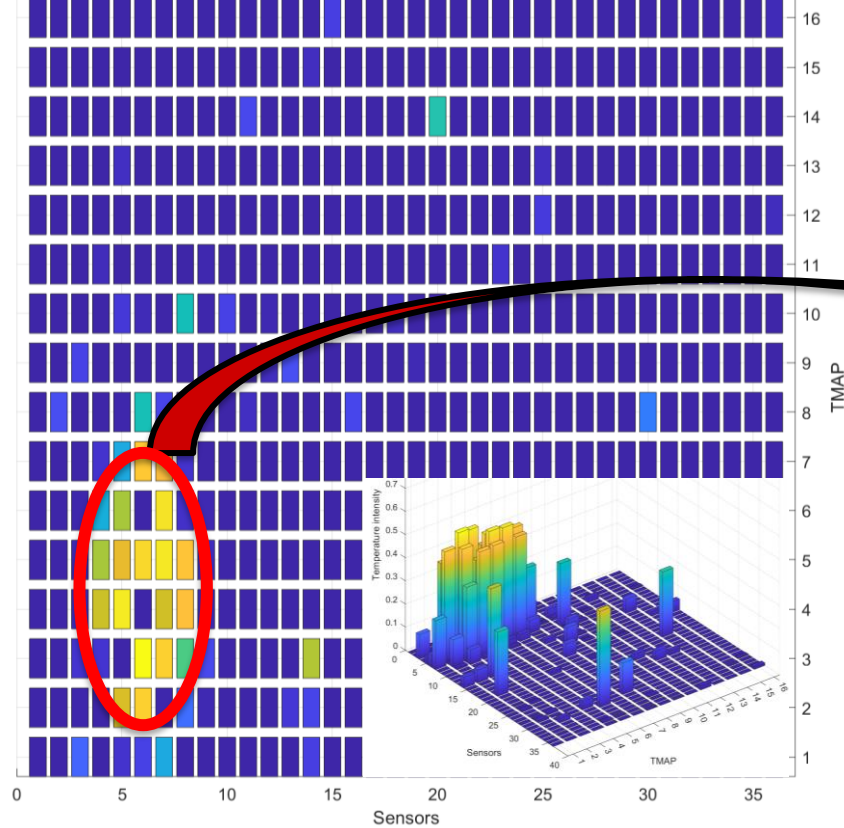


## TMAP system

- ❖ 36 boards
- ❖ 16 carbon resistive sensors (576 sensors)
- ❖ Measurement efficiency %35

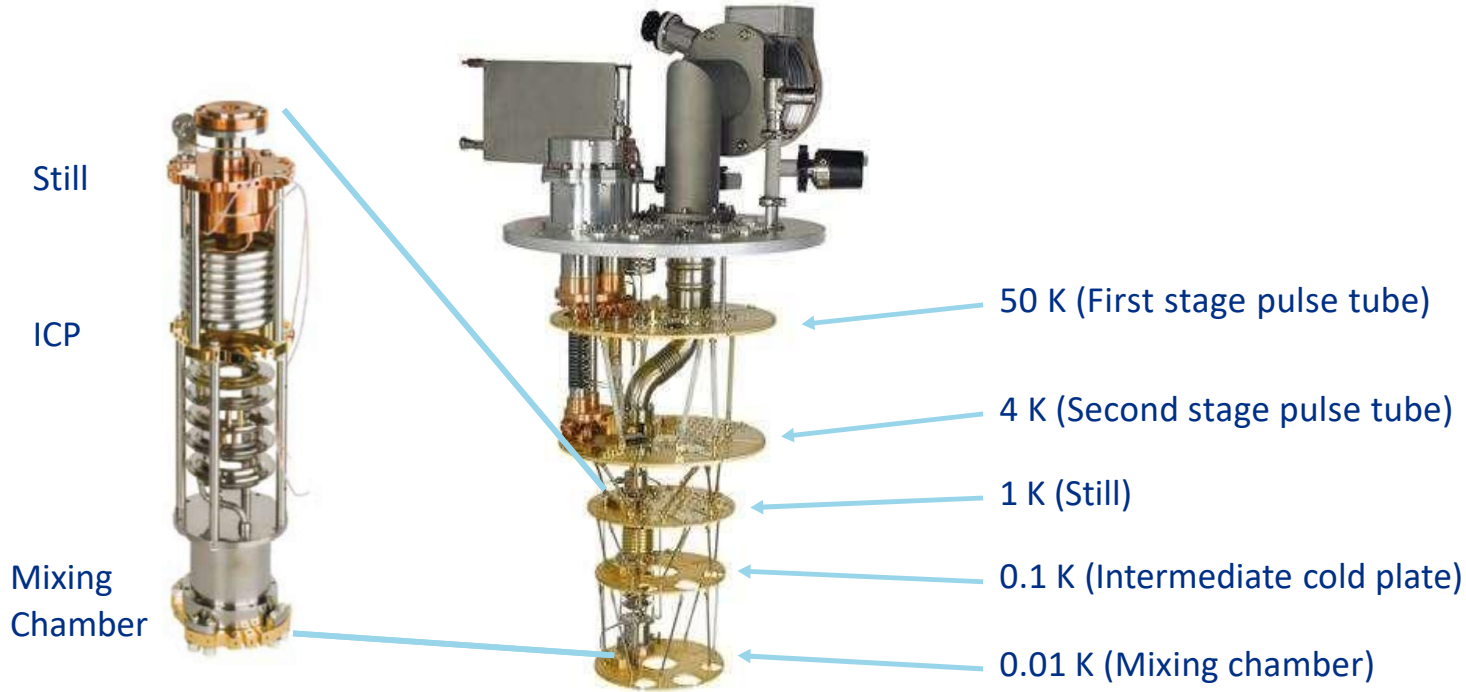
# Thermometry MAP

TMAP Eacc=9.045

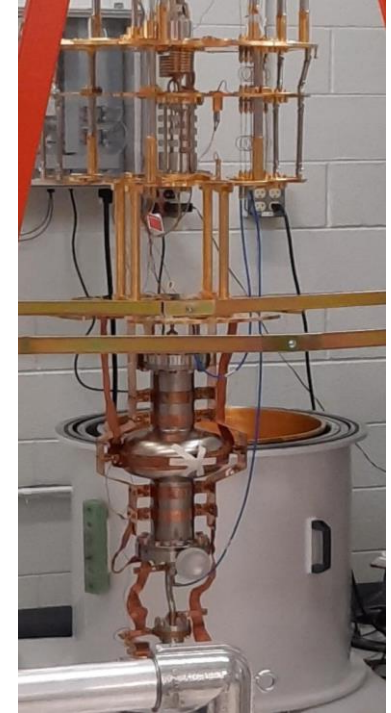




# Dilution Fridge (DR) cavity testing

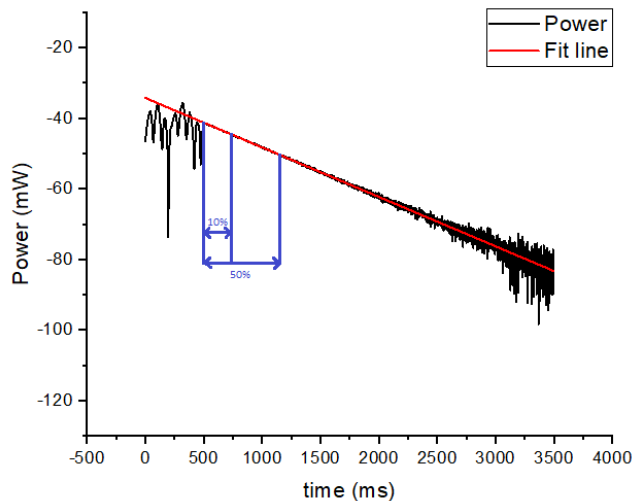


Images: Oxford Instruments

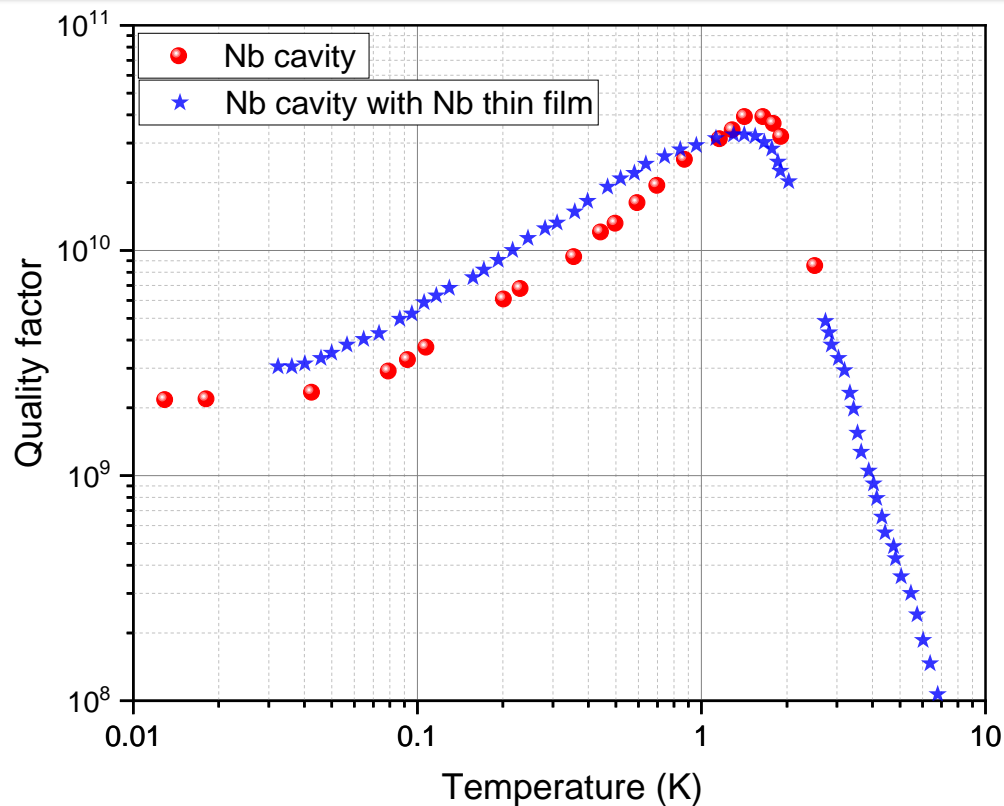


BlueFors dilution fridge system  
at Fermilab

# Quality Factor and Frequency dependence as a function of Temperature

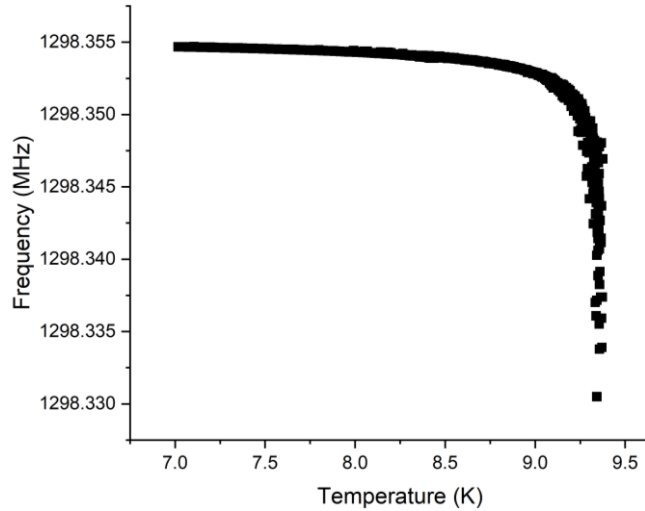


- ❖ The cavity was tested from **10K** down to **40mK** to measure the frequency and quality factor dependence as a function of temperature at low fields.
- ❖ The cavity performance was similar to that of bulk niobium cavities at the quantum regime.



Quality factor comparison of Nb cavity and Nb cavity with Nb thin film

# BCS Halbritter fitting MFP of Thin Film Nb on 1.3GHz Nb Cavity



Frequency versus Temperature

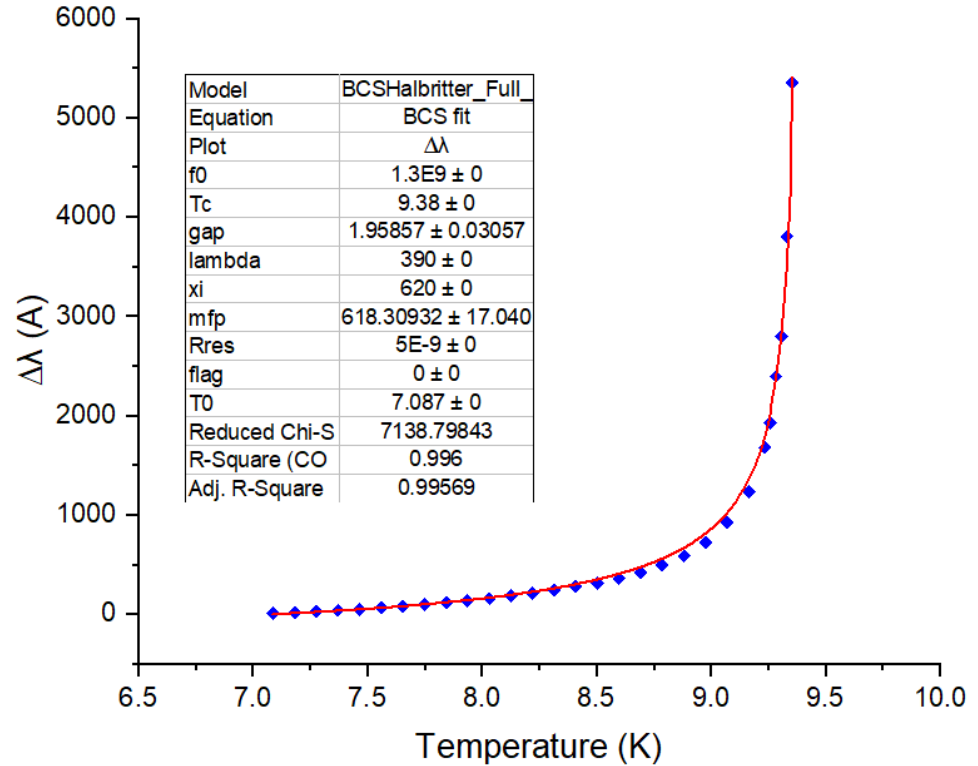
$$\Delta\lambda(T) = -\frac{G\Delta f_0(T)}{\mu_0\pi f_0^2(T_0)}$$

$\Delta\lambda$  is the shift in the penetration depth

$$\Delta f_0(T) = f_0(T) - f_0(T_0)$$

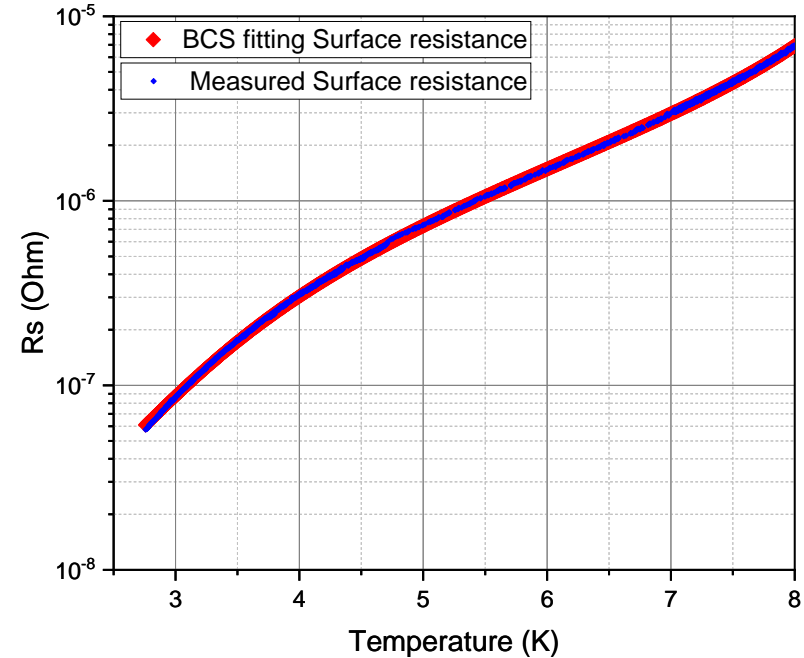
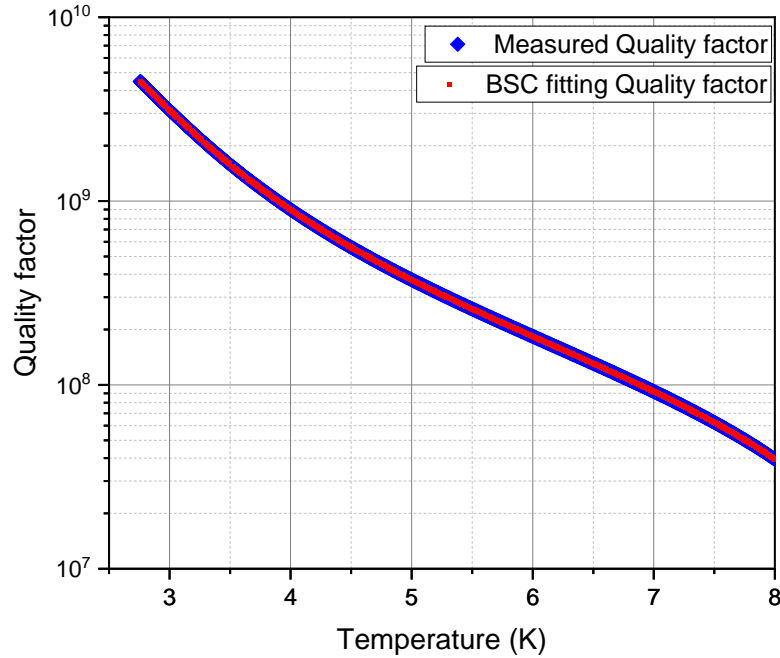
is the shift in the resonant frequency

$T_0 \approx 7$  K for niobium



BCS fitting on shift in penetration depth

# Measured and Calculated Q and Rs comparison



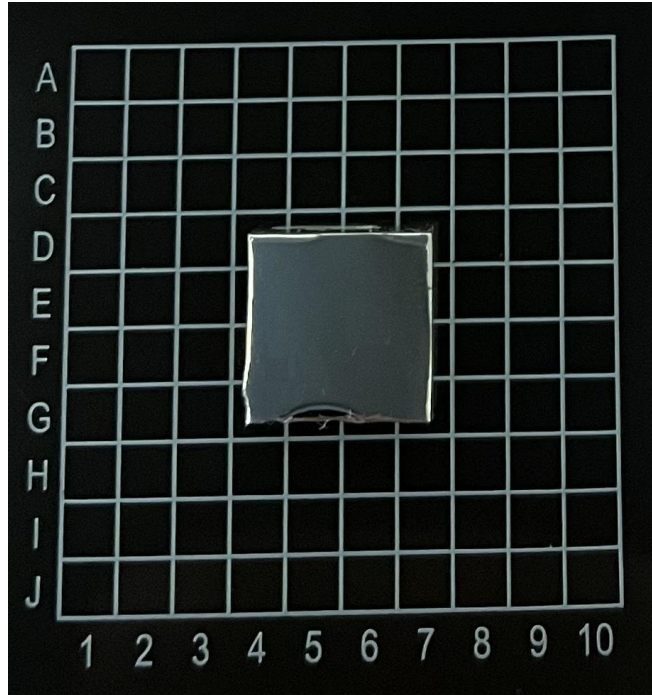
$$R_s = \frac{G}{Q} \quad \text{where } G \text{ is a geometry factor. (} G=273\Omega \text{)}$$



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**Characterization of Nb films.**  
**(microstructure, surface morphology, microwave properties, etc...)**

# Nb thin film on Nb substrate



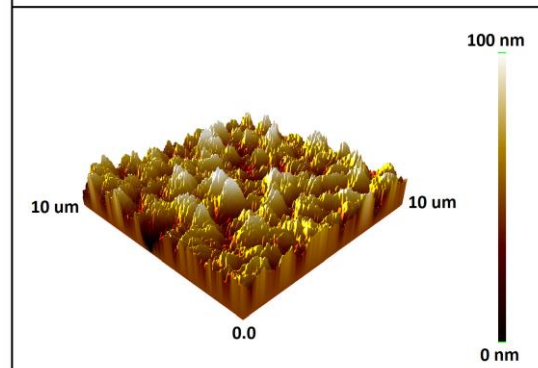
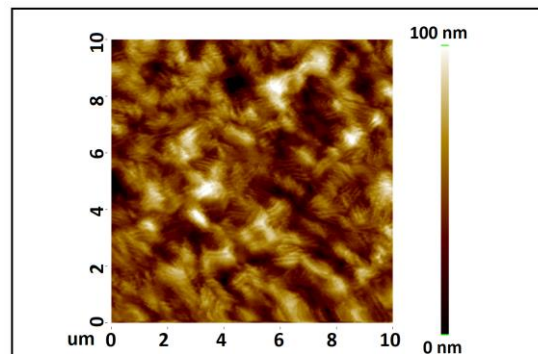
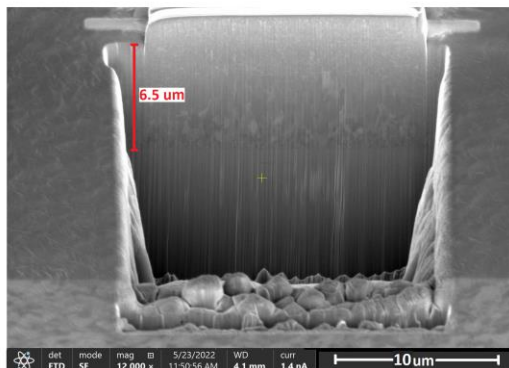
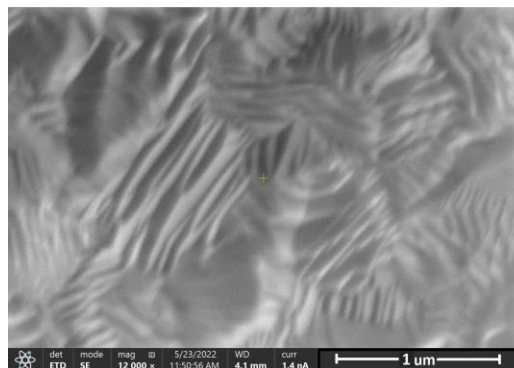
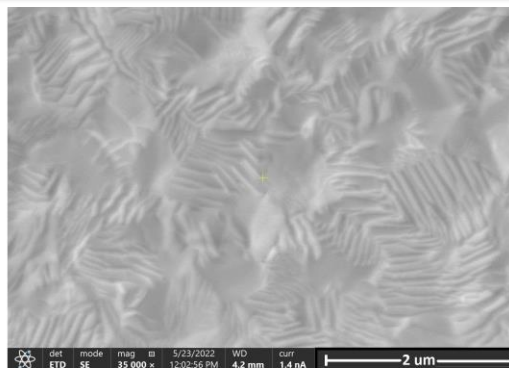
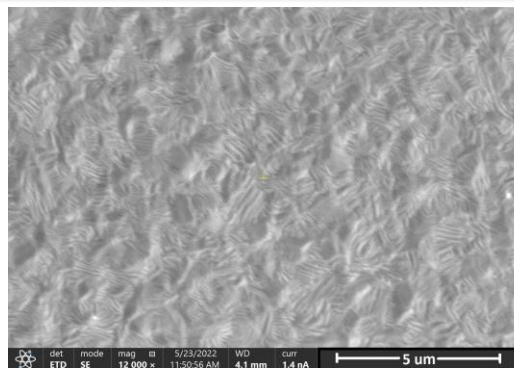
## Thin-film deposition parameters

- ❖ Main pulse duration: 200us
- ❖ Bias voltage: -75V
- ❖ Power: 1200W
- ❖ Pressure:  $3 \times 10^{-3}$  mbar
- ❖ Temperature: 150°C
- ❖ Deposition time: 6 hours
- ❖ Target: Nb RRR300
- ❖ Background gas: Kr
- ❖ Thickness: 6μm
- ❖ Substrate: Niobium (200)
- ❖ Substrate size: 1cm X 1cm

Data: CERN

❖ Nb thin films deposited on Nb substrates by using Bipolar HiPIMS with the same parameters at CERN.

# Surface morphology and thickness

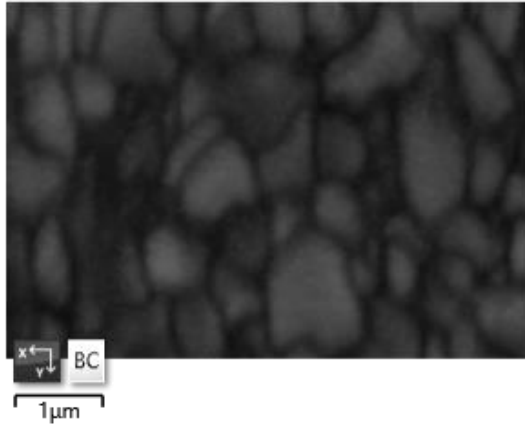


❖ RMS surface roughness is **13.4 nm** (scanned area 10 μm X 10 μm)

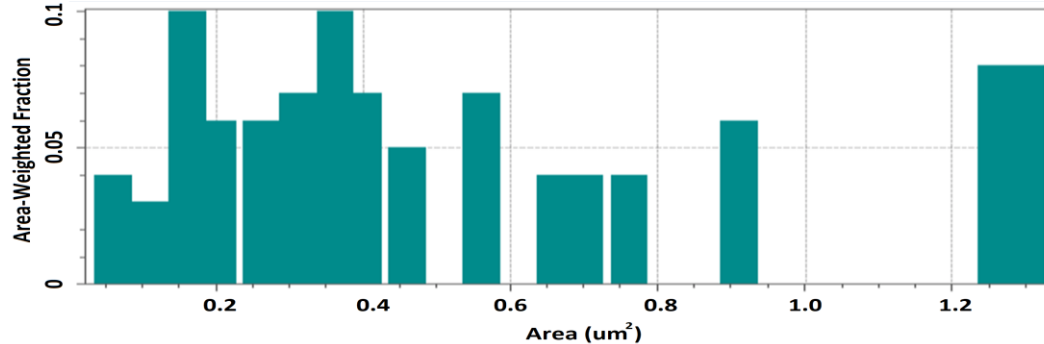
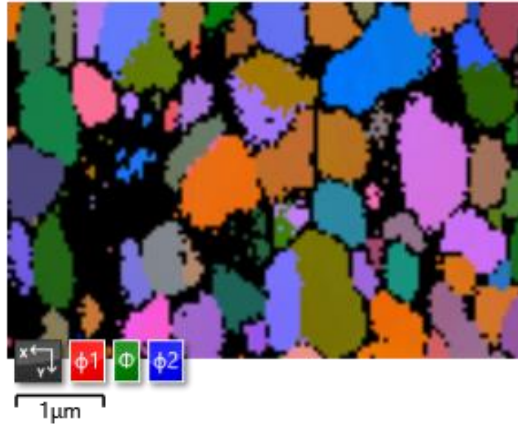
❖ Thickness is **6.5 μm**

# Grain size and orientations

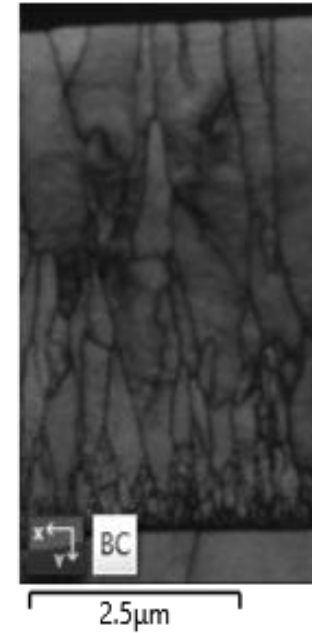
Band contrast



Euler color



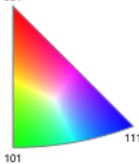
Band contrast



Euler color

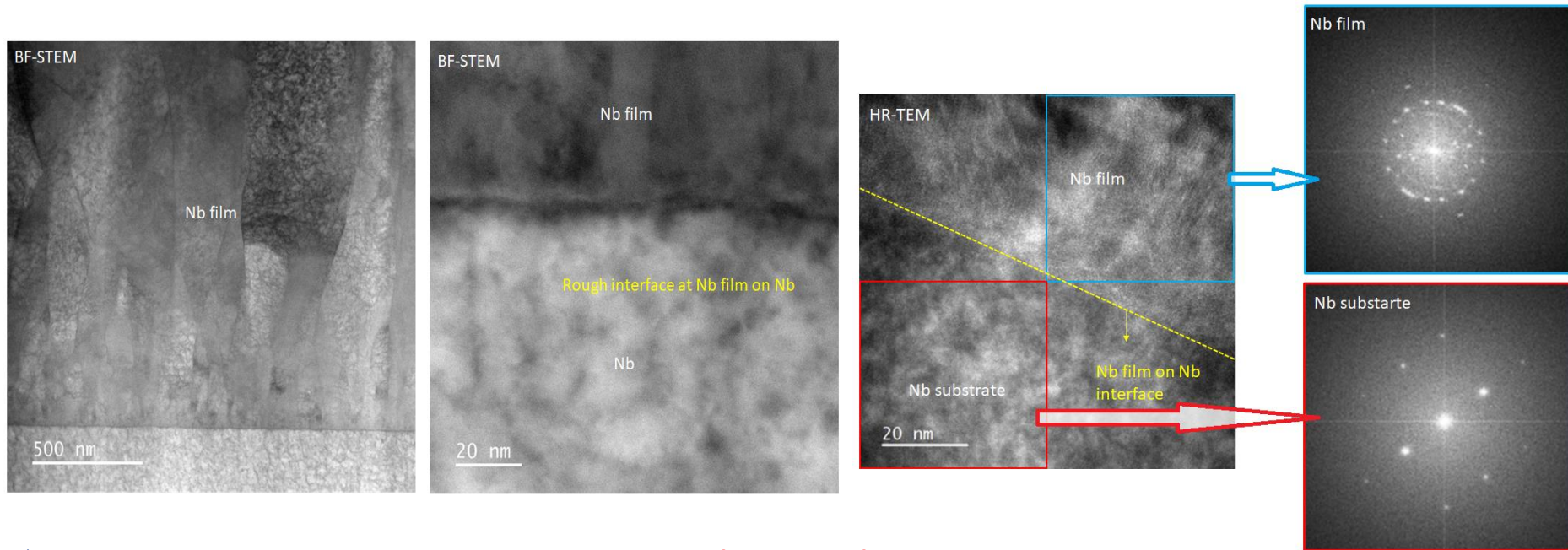


Transmission EBSD



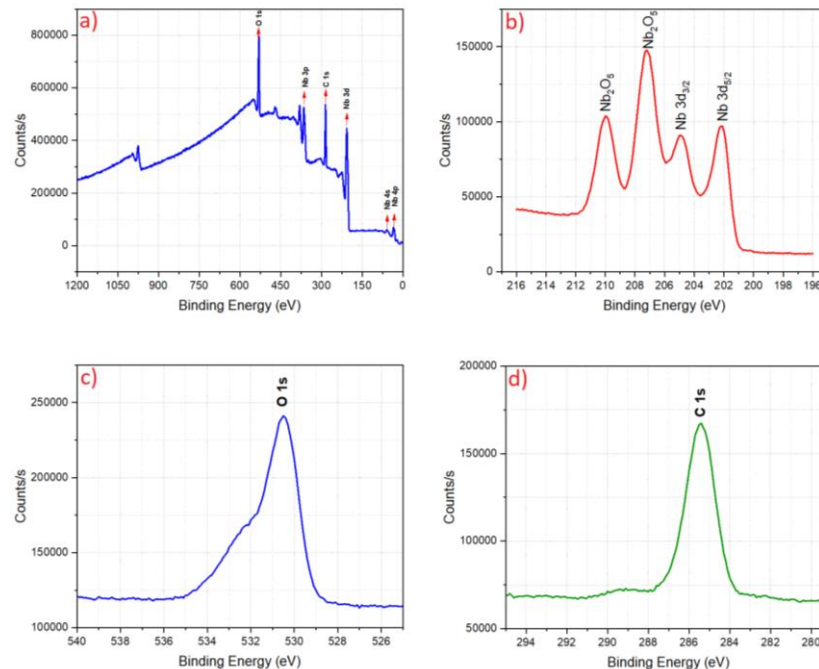
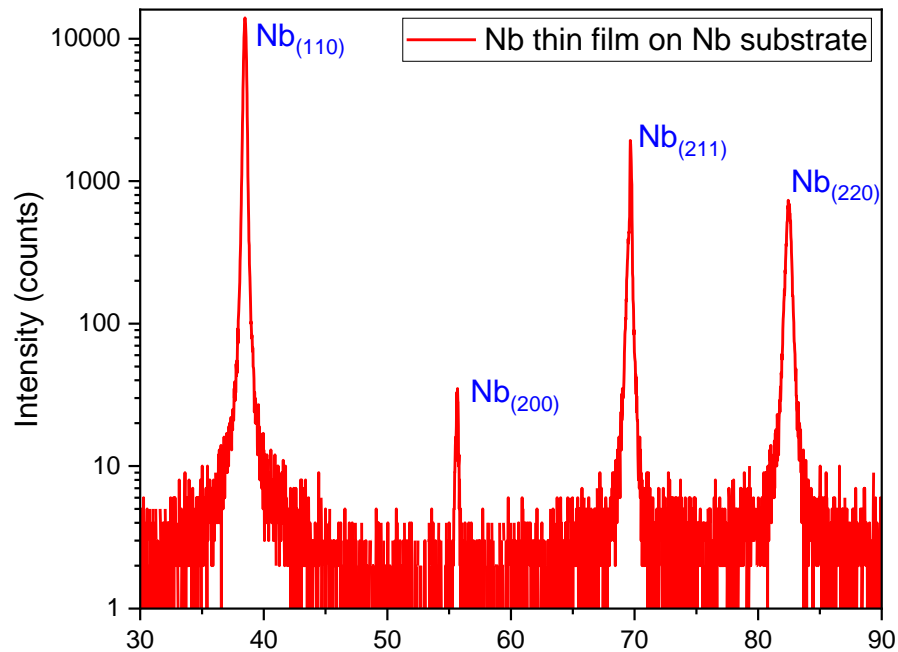


# Oxygen layer detected by high-resolution TEM



- ❖ The growth type of the thin film is **Volmer-Weber (3D islands)**.
- ❖ The oxygen layer **prevents epitaxial growth**.
- ❖ Nb films grow **randomly** on the Nb substrate.

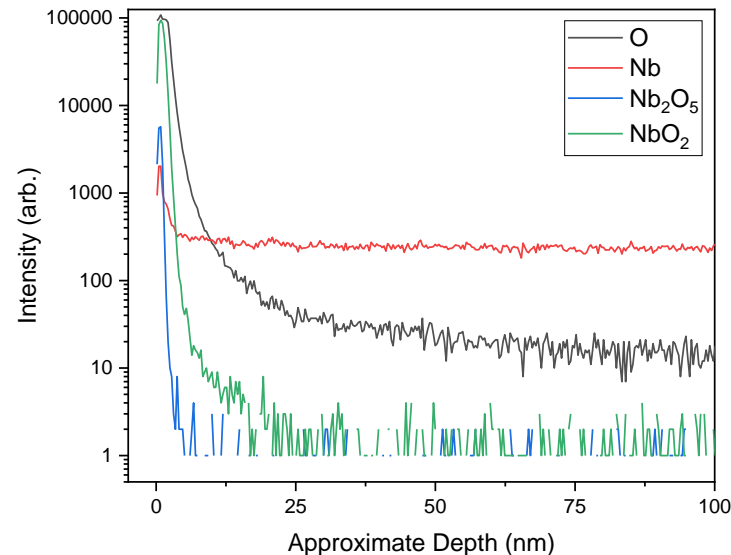
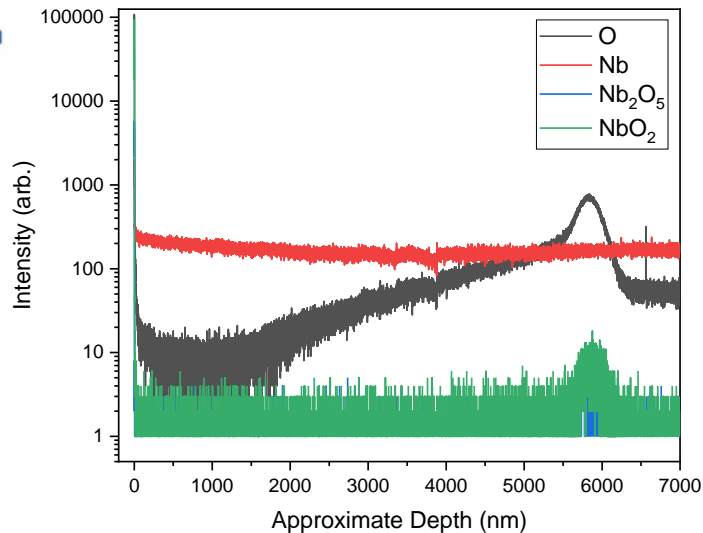
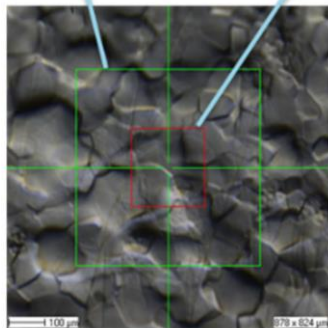
# Crystallographic orientation and concentration of the elements



- ❖ The thin film was polycrystalline dominated by Nb (110) orientation. Nb (200), Nb(211), and Nb (220) oriented structures were detected
- ❖ The concentration of elements showed that C, 52.51%; O, 32.06%; and Nb, 15.43% on the surface

# High concentrated oxygen layer on the surface and at the interface

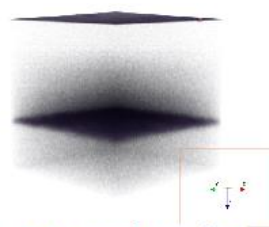
Sputtering area      Analysis area



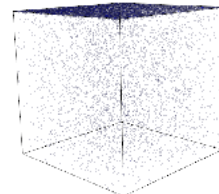
- ❖ 500 μm x 500 μm sputter area
- ❖ 200 μm x 200 μm analysis area



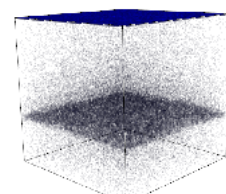
3D render of Nb



3D render of O



3D render of Nb<sub>2</sub>O<sub>5</sub>



3D render of NbO<sub>2</sub>

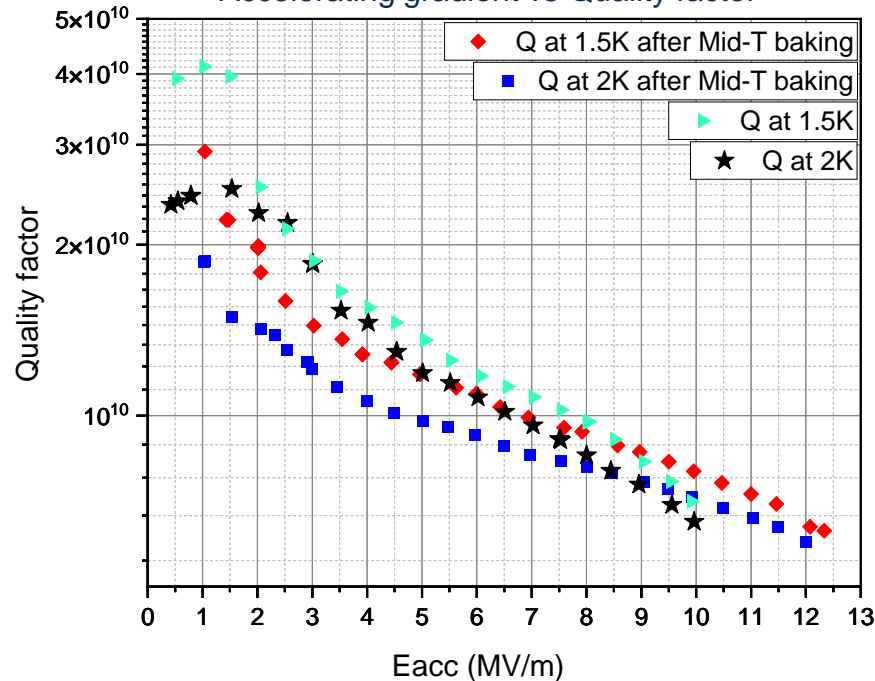
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**Cavity performance after Mid-T baking at 340°C for 1 hour.**

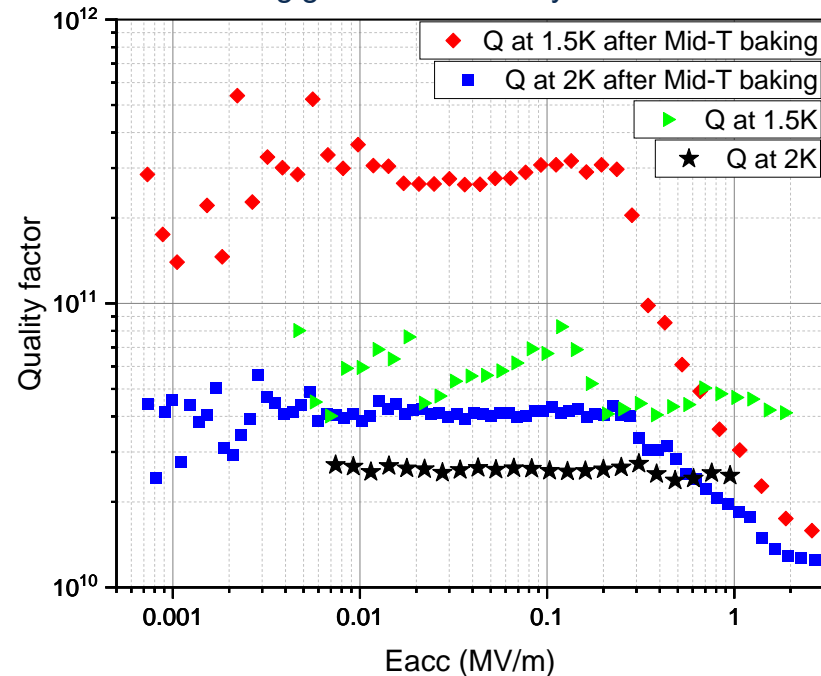


# What changed after Mid-T baking?

Accelerating gradient vs Quality factor

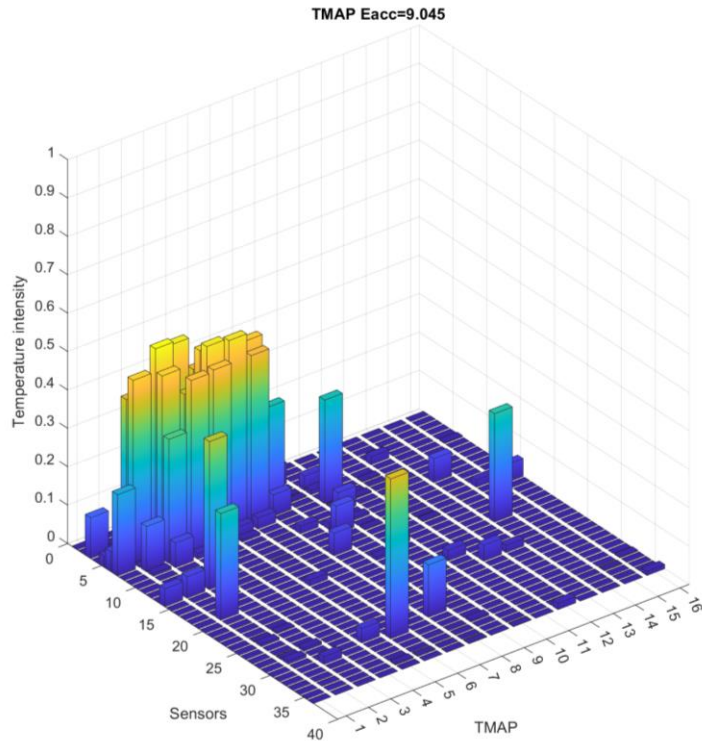


Accelerating gradient vs Quality factor at low field

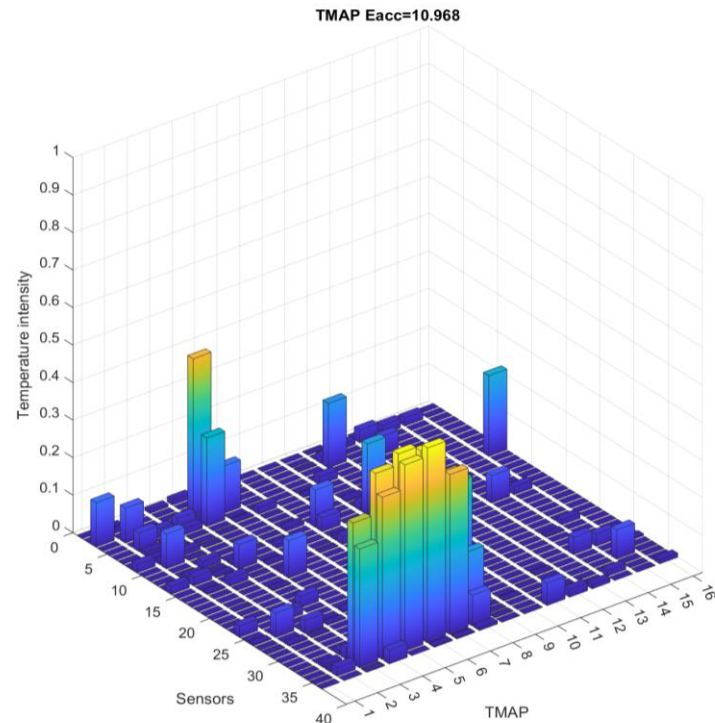


- ❖ After “*in-situ*” Mid-T baking at 340°C for 1 hour, the cavity was limited at  $E_{acc} \approx 12.8$  MV/m by a quench.
- ❖ Quality factor increased by factor 10 at the low field at 1.5K after Mid-T baking.

# Thermometry MAP

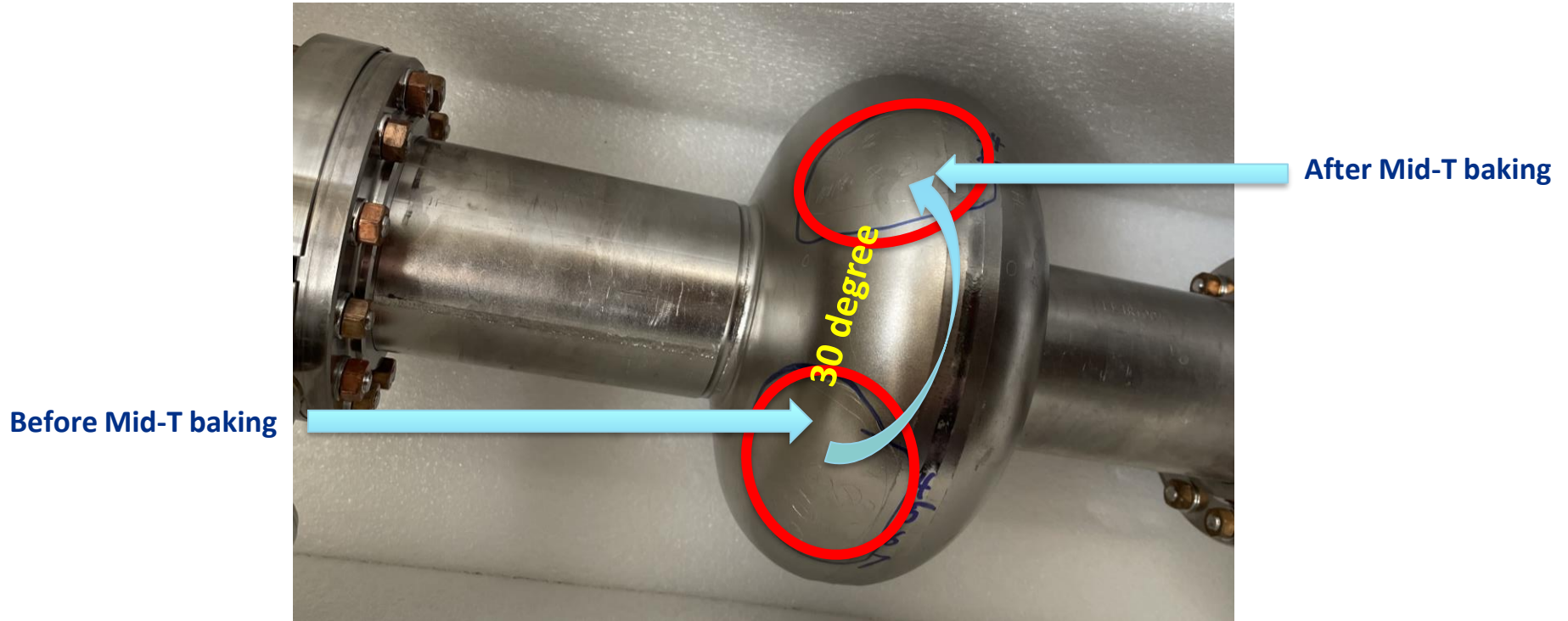


Hot spot area before Mid-T baking



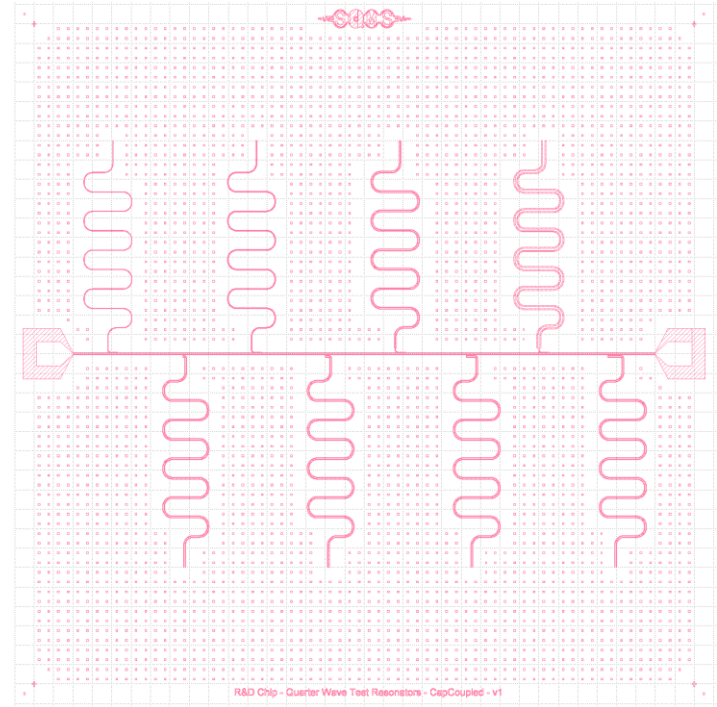
Hot spot area after Mid-T baking

# Hot spot area on the cavity



# What is next?

- ❖ Dilution fridge (DR) test after Mid-T baking.
- ❖ Nitrogen doping treatment.
- ❖ VTS and DR tests after Nitrogen doping treatment.
- ❖ Create coplanar quarter wave 2D resonators by using Nb (RRR300) thin films deposited on sapphire substrates with different PVD systems.



Designed quarter-wave resonators inductively coupled with a single 50Ω feedline.



# Conclusion

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- ❖ The cavity performance was similar to that of bulk niobium cavities at the quantum regime. At mid and high field, the quality factor of the Nb thin film cavity was lower than the bulk Nb cavity.
- ❖ Nb Thin film was polycrystalline dominated by the Nb (110) orientation. Nb (200), Nb(211), and Nb (220) structures were detected. The root mean square (RMS) of surface roughness is 13.4 nm.
- ❖ The conventional method of concentration of elements showed that C, 52.51%; O, 32.06%; and Nb, 15.43% on the surface. At the surface of the film and the intersection, an oxide layer was observed. The oxide layer at the intersection prevented epitaxial thin film growth.
- ❖ The cavity was limited at  $E_{acc} \approx 10.2$  MV/m by a quench. After Mid-T baking, it increased to  $E_{acc} \approx 12.8$  MV/m. The heated local area is not at the equator as expected. After Mid-T baking, it moved to a different area.
- ❖ At the low field, the quality of the cavity increased by factor 2 at 2K and it increased approximately 10 times at 1.5K after Mid-T baking.

# Thank you



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